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(54) **METHOD AND APPARATUS FOR ELLIPSOMETRY MEASUREMENT**

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(2013.01)

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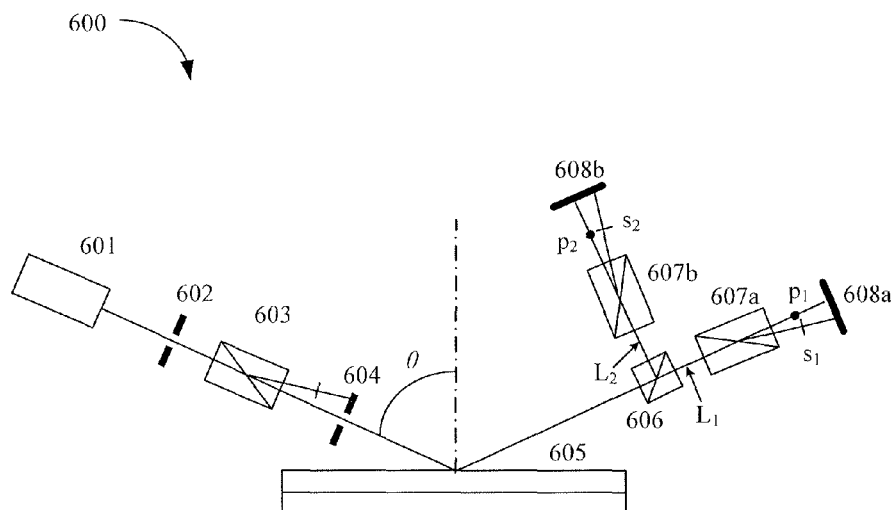
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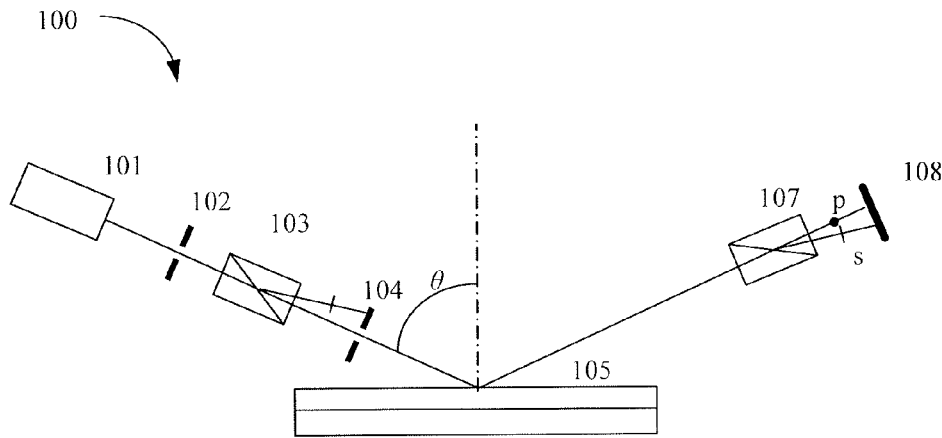
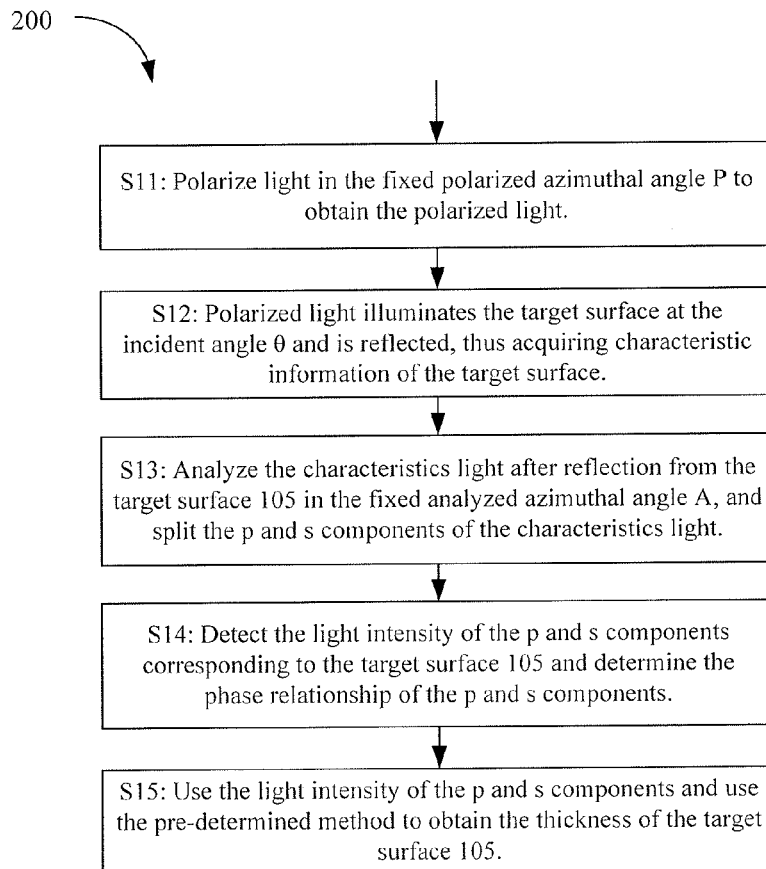
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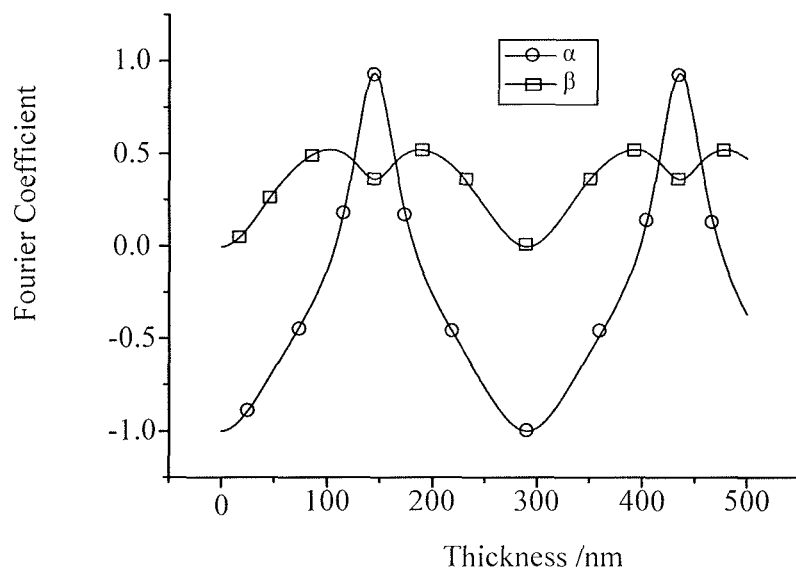
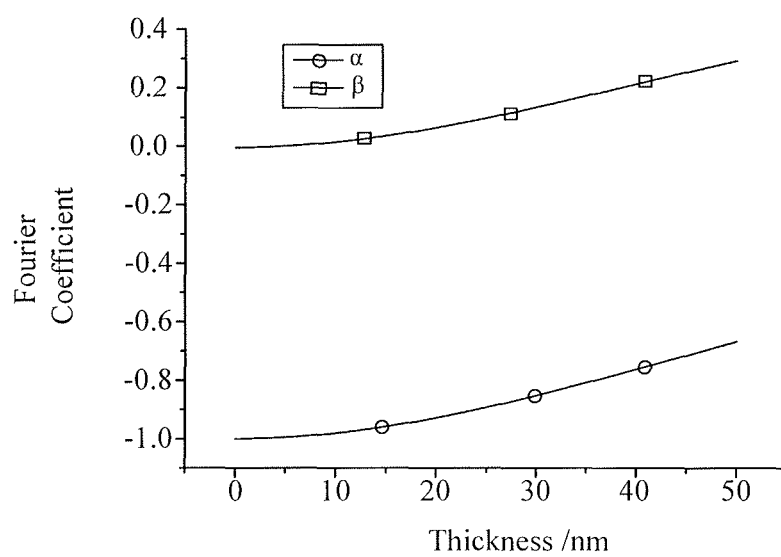
(57) **ABSTRACT**

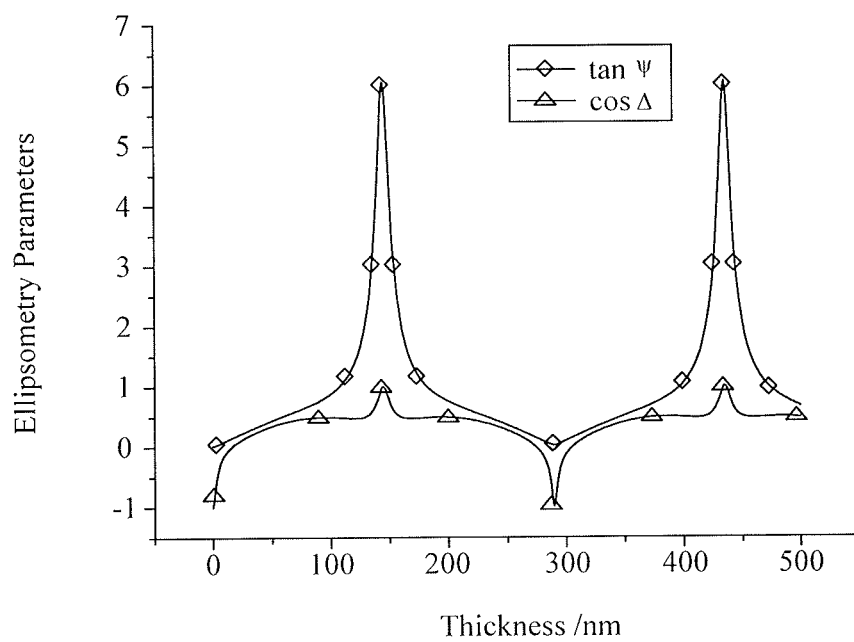
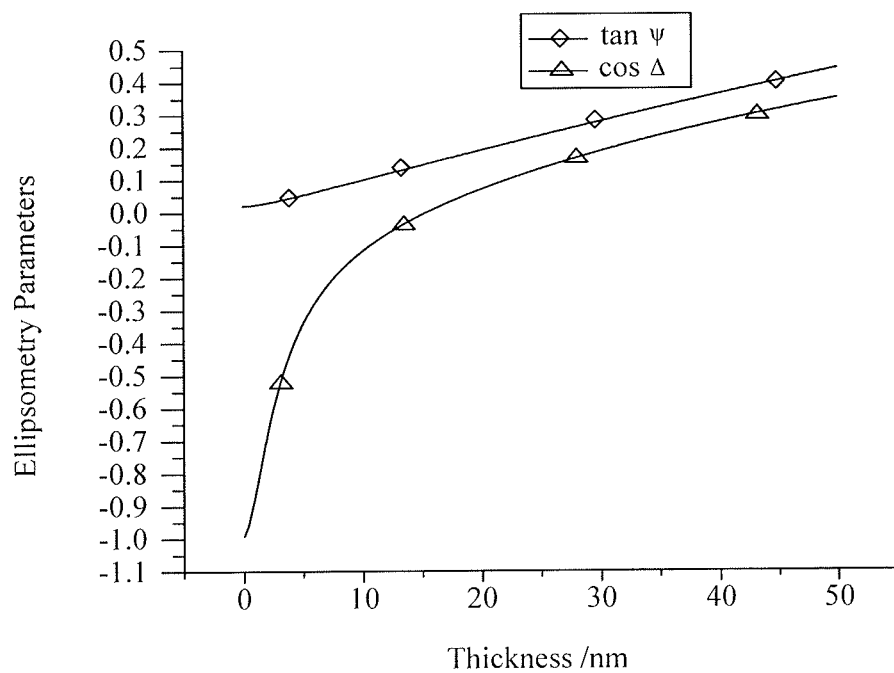
Methods and systems are provided to avoid the rotation action with the polarizer and the analyzer in complex ellipsometric measurement and repeated processes. In particular, methods and systems are provided which polarize the incident light in a fixed azimuthal angle then illuminate the polarized light onto the target surface, analyze the surface polarized characteristics light in a fixed azimuthal angle, and obtain the light intensity and phase information corresponding to the target surface. Then, based on the relationship between the characteristic information detected by electromagnetic wave and the light intensity information, the disclosed methods and systems obtain the characteristic information of the target surface.

14 Claims, 8 Drawing Sheets



**Fig. 1****Fig. 2**

**Fig. 3a****Fig. 3b**

**Fig. 4a****Fig. 4b**

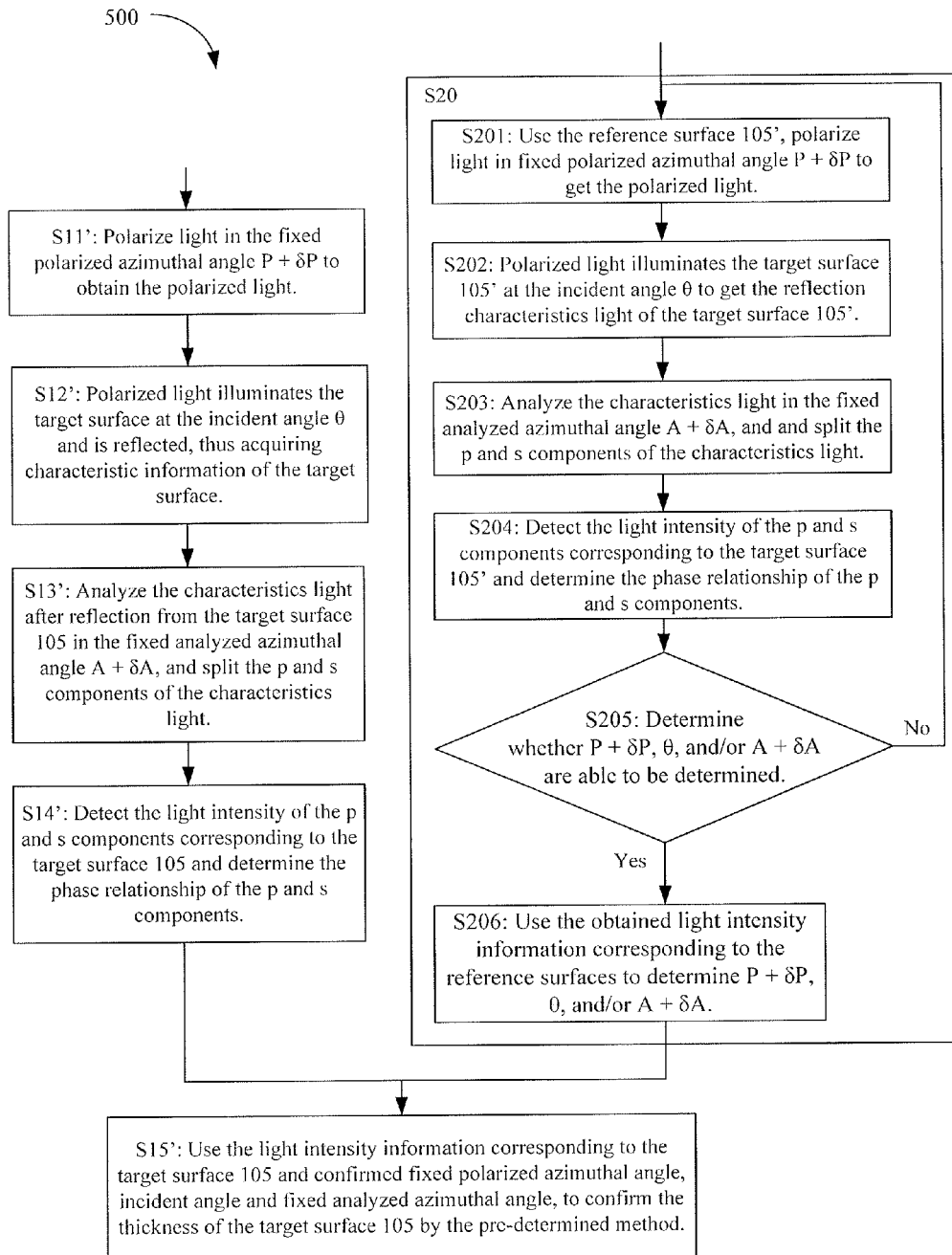


Fig. 5

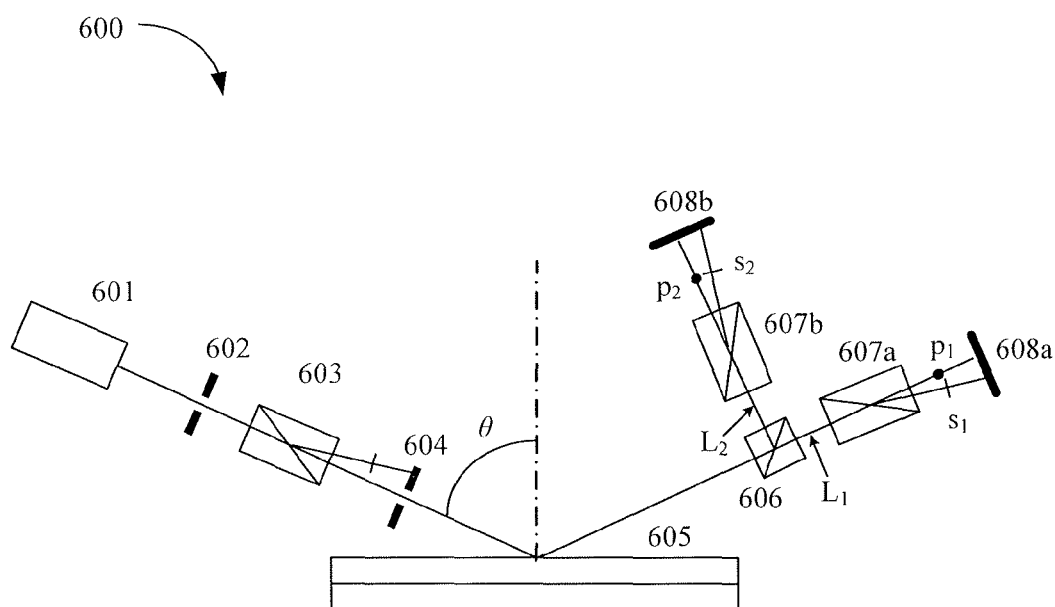
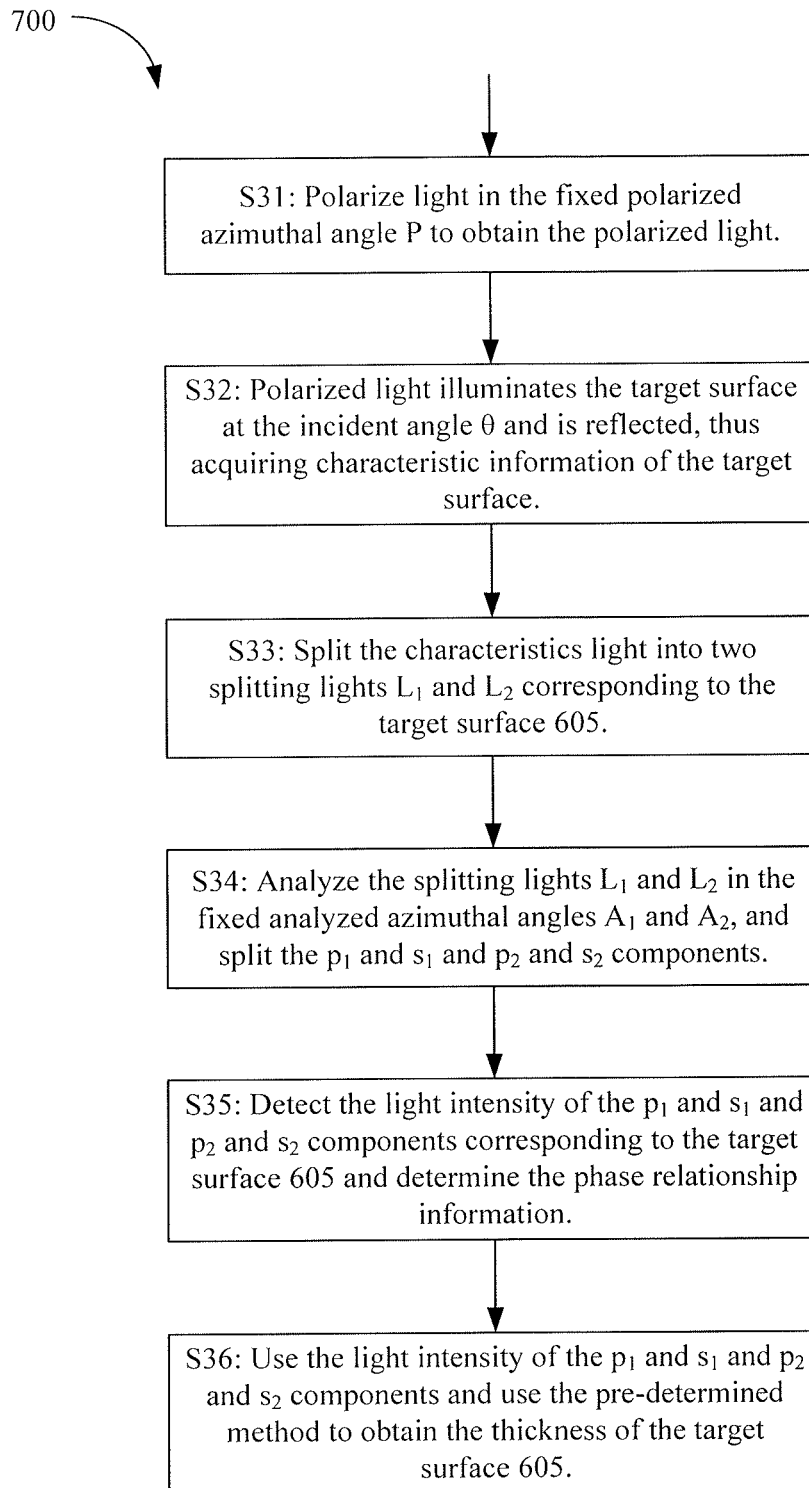


Fig. 6

**Fig. 7**

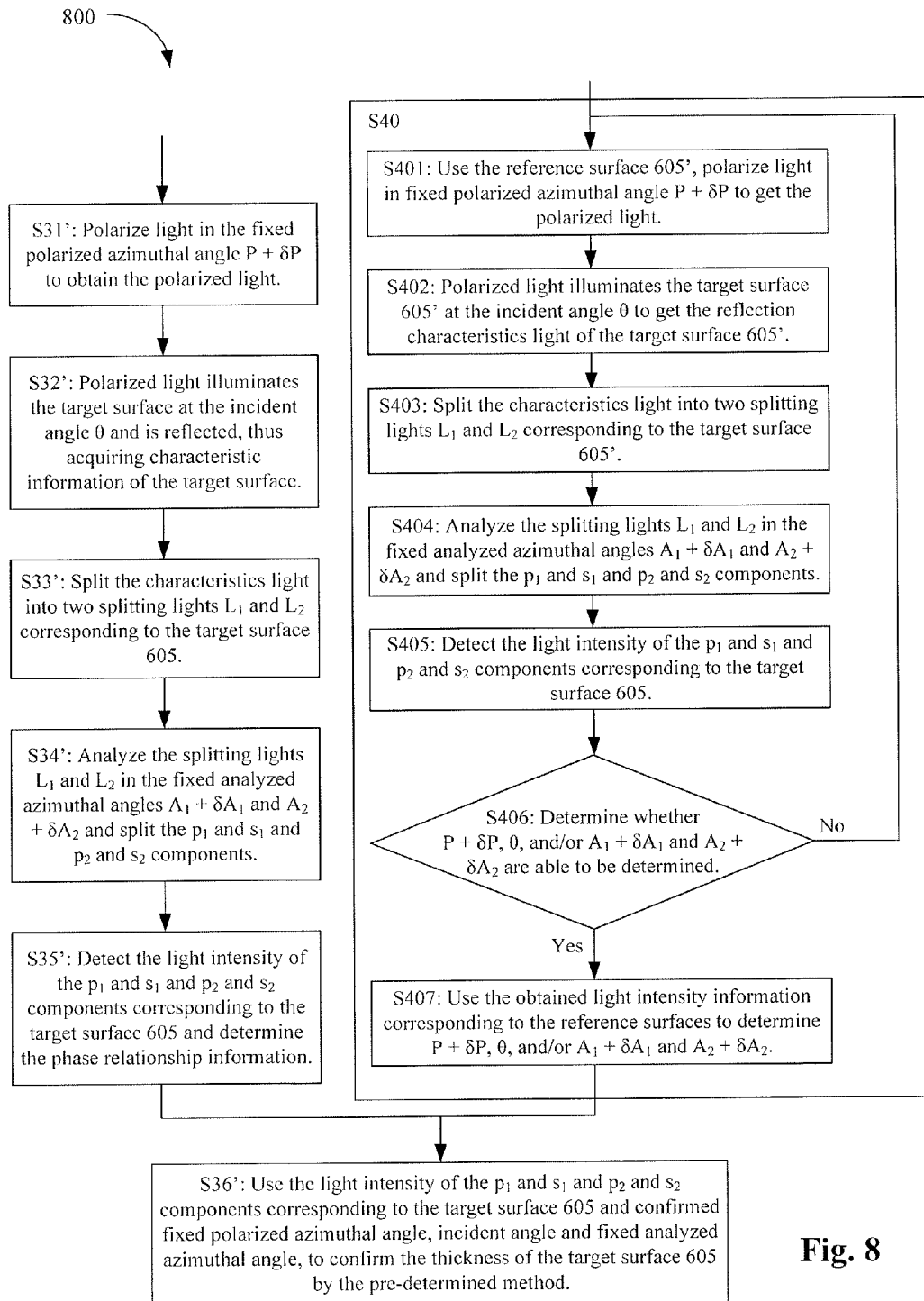
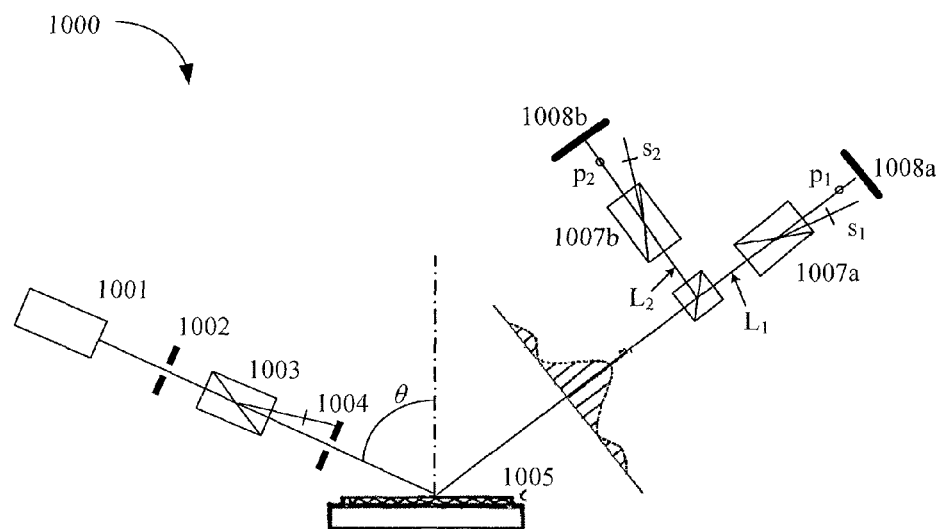
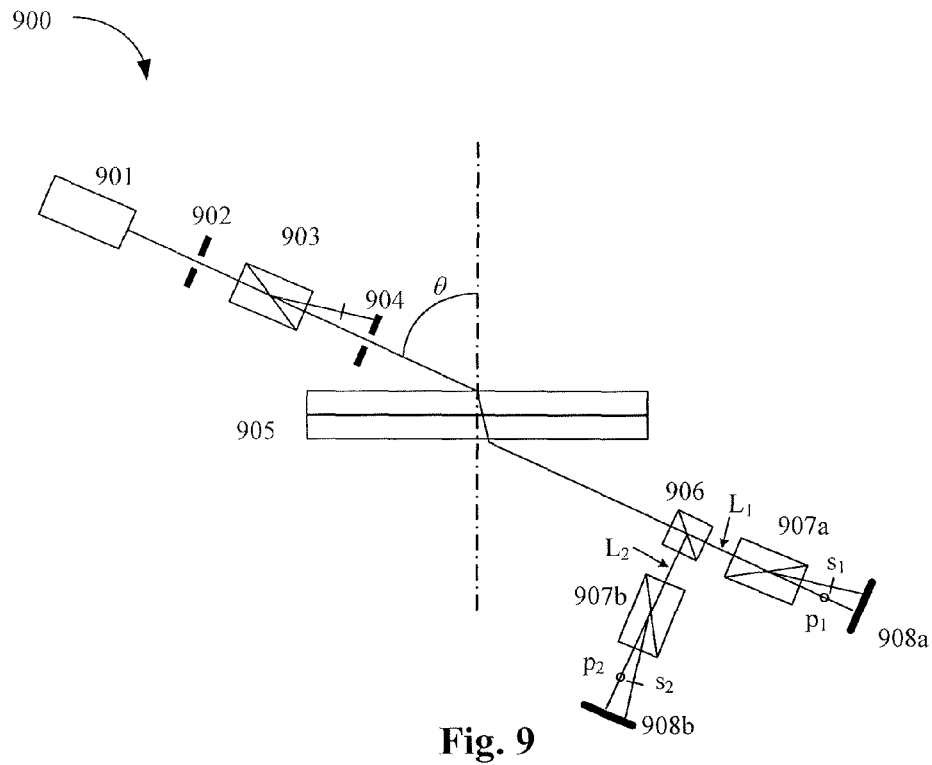


Fig. 8



1

METHOD AND APPARATUS FOR ELLIPSOMETRY MEASUREMENT

FIELD OF THE INVENTION

This application generally relates to optical measurement methods, and more particularly relates to measuring methods and apparatuses utilizing ellipsometric techniques on semiconductor devices and wafer surfaces and other materials.

DESCRIPTION OF THE BACKGROUND ART

The ellipsometric technique is a powerful multi-functional light division technology, used to obtain characteristics information about target surfaces by detecting electromagnetic waves. The characteristics information may include reflectivity, thickness, refractive index, extinction parameters, polarization, surface microstructure, particles, defects, and roughness of the target surface or the thin film surface, and so on. Because the ellipsometric technique is a highly sensitive, non-destructive, and no-contact measurement technique, it is widely used in a variety of fields from basic research to industrial applications, including semiconductor physics, microelectronics, and various areas of biology.

Existing ellipsometric measurement technology works as follows: A light source emits light which passes through a first polarizing plate (often called the polarizer) to generate a polarized light. Then the polarized light illuminates a target surface. The polarized light changes its polarization state after interacting with the target surface. The light then passes through a second polarizer (often called the analyzer), and then enters a detecting device. The ellipsometric technology analyzes light intensity, phase, and polarization states of the light reflected by the target samples, and accordingly obtains the characteristics information that is detected by the electromagnetic waves as they interact with the target surface. This technique works even if the thickness of the target is shorter than the wavelength of the detecting light, e.g., a thickness that is equal or even less than a single atomic layer.

In general, ellipsometry is a technique based on light mirror reflection, in which the incident angle is equal to the reflection azimuthal angle, and the incident light path and the reflected light path are in the same plane (called the incident plane). In the text to follow, the components of the electric field of the polarized light that are parallel with and perpendicular to this incident plane are respectively defined as "p" and "s" components of the polarized light. The polarization state of the polarized light upon interaction with the target surface can change due to various mechanisms, including reflection, transmission, diffraction, and so on. In this application, without loss of generality, the main conditions for reflection are introduced. Because in existing ellipsometry techniques, each measurement can only obtain one set of experimental data, these techniques generally use a rotating ellipsometry method. According to this method, a first motor rotates the polarizer to change the polarizer's azimuthal angle. Similarly, a second motor rotates the second polarizer (the analyzer) to change the analyzer azimuthal angle. Based on all the polarizer azimuthal angles, a set of data can be obtained, and accordingly the characteristics of the target surface can be determined. Therefore, since the existing techniques require a set of data, these techniques suffer some shortcomings, such as long data measuring time, method complexity, and expensive hardware.

SUMMARY OF THE INVENTION

Various embodiments address problems, such as long time data measuring, complex measuring method and expensive

2

measuring hardware caused by rotating the polarizer. In various embodiments, the ellipsometric technique polarizes the light from the light source in a certain azimuthal angle, and then the polarized light is directed onto the target surface.

After being reflected by the target surface, the light characteristics could be interpreted based on some relationship information. Finally, based on the obtained light intensity of the reflected light, the characteristics information of the target surface could be determined. In the traditional systems, when conducting the measurement, there always exist deviations in the polarized azimuthal angle, the incident angle, and the analyzed azimuthal angle. To avoid such deviation, various embodiments provide a reference surface for calibration before the measurement for the target surface's characteristics begins.

BRIEF DESCRIPTION OF THE DRAWINGS

In the following detailed description, the character, target, and advantages will be shown better. In the drawings, same or similar drawings stand for same or similar steps or units or devices.

FIG. 1 shows a light division ellipsometry system based on surface reflection in accordance with an embodiment.

FIG. 2 illustrates a method of ellipsometric measurement in accordance with an embodiment.

FIG. 3a shows variations of the Fourier coefficients as a function of the thickness of the target in accordance with an embodiment.

FIG. 3b shows variations of the Fourier coefficients as a function of the thickness of the target in accordance with an embodiment.

FIG. 4a shows the variations in ellipsometry parameters as a function of the thickness of the target in accordance with an embodiment.

FIG. 4b shows the variations in ellipsometry parameters as a function of the thickness of the target in accordance with an embodiment.

FIG. 5 illustrates a method of ellipsometric measurement, which includes calibration, in accordance with an embodiment.

FIG. 6 shows a light division ellipsometric system based on surface reflection for determining the characteristics information in accordance with an embodiment.

FIG. 7 shows a flow chart for a light division method for detecting characteristics information of a surface via the electromagnetic waves in accordance with an embodiment.

FIG. 8 illustrates a method of ellipsometric measurement, which includes calibration, in accordance with an embodiment.

FIG. 9 shows a measurement system in accordance with an embodiment.

FIG. 10 shows a measurement system in accordance with an embodiment.

DETAILED DESCRIPTIONS OF THE PREFERRED EMBODIMENTS

Based on FIGS. 1 to 10, the following detailed description describes several embodiments.

First Embodiment

FIG. 1 shows a light division ellipsometry system 100 based on surface reflection in accordance with the first embodiment. The system includes a light source 101, a first condenser hole 102, a polarizer 103 (at azimuthal angle 45

3

degrees), a second condenser hole **104**, a target surface **105**, an analyzer device **107**, and a detection-processing device **108**. Also, in system **100**, detection-processing unit **108** is connected to a computing device and a calibration device, which are not shown in FIG. 1.

In FIG. 1, the azimuthal angle of polarizer **103** is 45 degrees, and the azimuthal angle of analyzer **107** is 0 degrees. Consistent with an embodiment, target surface **105** may be a SiO₂ film. Detection-processing unit **108** receives the output of analyzer **107**, namely, p and s components of the light, and detects the light intensity information to obtain the p and s components and the phase relationship between the components. Moreover in FIG. 1, polarized light incident angle θ is near the target surface Brewster azimuthal angle.

Consistent with an embodiment, light source **101** may be a He—Ne laser for which the output wavelength is 632.8 nm. However, light source **101** can use other types of light sources as known by persons of ordinary skill in the art, for example, high-power red LED light sources.

In FIG. 1, first condenser hole **102** is used to better focus the incident light, and hole **104** is used to avoid partial outputs from other polarized light beams into the measurement light path. Use of holes **102** and **104** improves the accuracy of measurement. However, as understood by persons of ordinary skill in the art, hole **102** or hole **104** is not necessary to implement embodiments.

FIG. 2 illustrates a method **200** of ellipsometric measurement in accordance with an embodiment. The method **200** may be performed on a target surface SiO₂ film, as further described in relation to FIGS. 2, 3a, and 3b. Consistent with an embodiment, a characteristic of the target surface is the thickness of the target. The light source **101** emits light, the emitted light goes through condenser hole **102** and is focused by hole **102** and then illuminates polarizer **103**.

In step **S11**, polarizer **103** polarizes a single wavelength light at a fixed polarizer azimuthal angle P to generate a single wavelength polarized light.

Then, the polarized light goes through second condenser hole **104**. Second condenser hole **104** only allows one polarized light passed through polarizer **103**, and blocks the rest of polarized lights in order to avoid their impact on the measurement.

In step **S12**, the polarized light is incident at the incident angle θ onto target surface **105**. As known by persons of ordinary skill in the art, without second condenser hole **104**, the light path of the polarized light passed through polarizer **103** may be quite different from the light path of the polarized light passed through second condenser hole **104** as shown in FIG. 1. However, in the first case, the additional light will not be reflected by target surface **105** and thus will not reach analyzer device **107**. So, the effect to the measurement result can be ignored or even this effect will not be generated. Thus, as mentioned above, second condenser hole **104** is not necessary.

The illuminated polarized light is reflected by target surface **105** and reaches analyzer **107**. After the reflection, the nature of the polarized light changes due to the target surface **105**, and acquires the characteristic information of the target surface. In the step **S13**, analyzer **107** analyzes the characteristics light reflected by the target surface **105** in the fixed analyzer azimuthal angle A . Analyzer **107** separates the p component and the s component of the characteristic light and provides them to the detection-processing device **108**.

In step **S14**, detection-processing device **108** receives and detects the light intensity of the p component and the s component of the characteristics light, obtains light intensity information corresponding to the target surface **105**, and

4

obtains the phase difference between the p component and the s component. Detection-processing device **108** provides the obtained light intensity information to calculation device **109**, which has an electromagnetic connection with the detection-processing device **108** and is not shown in FIG. 1. Specifically, detection-processing device **108** may include a light intensity detecting device and a processing device, wherein the light intensity detecting device is used to detect the light intensity of the p component and the s component of the detected characteristics light, and the processing device is used to obtain the phase difference between the p component and the s component. The processing device may be a micro processing device, executing appropriate programs to calculate the phase difference information. The processing device may include firmware, ASIC, or DSP devices. The specific method of detection of light intensity and calculation of p and s components of the phase component is known to persons of ordinary skill in the art.

Finally, in step **S15**, calculating device **109** determines the thickness of the target surface **105** based on the light intensity of the p and s components of the characteristic light. As can be understood by persons of ordinary skill in the art, there are several ways to determine the thickness information, not limited by ways shown in this embodiment. Consistent with an embodiment, the principles of the determination are as follows.

The basic formula for the intensity of the output light after passing through polarizer **103** and analyzer **107** is,

$$I_{out}(P, A) = \left(\frac{1 + \frac{\tan^2 \Psi - \tan^2 P}{\tan^2 \Psi + \tan^2 P} \cos 2A + \frac{2 \tan \Psi \tan P \cos \Delta}{\tan^2 \Psi + \tan^2 P} \sin 2A}{\tan^2 \Psi + \tan^2 P} \right) \quad (1)$$

In equation (1), $P = \pi/4$, $A = 0$, $\tan \Psi$ is the amplitude ratio of the p and s components of the light, and Δ is the phase difference between the p and s components of the characteristics light. Light intensities $I_{out}(\pi/4, 0)$ and $I_{out}(\pi/4, \pi/2)$ can be used to calculate the Fourier coefficient

$$\alpha = \frac{\tan^2 \Psi - 1}{\tan^2 \Psi + 1},$$

and to further calculate the ellipsometry parameters $\tan \Psi$, that is:

$$\alpha = \frac{I(\pi/4, 0)_{out} - I(\pi/4, \pi/2)_{out}}{I(\pi/4, 0)_{out} + I(\pi/4, \pi/2)_{out}} \quad (2)$$

$$\tan \Psi = \frac{I(\pi/4, 0)_{out}}{I(\pi/4, \pi/2)_{out}}$$

Moreover,

$$\beta = \frac{2 \tan \Psi \cos \Delta}{\tan^2 \Psi + 1}$$

is the first-order Fourier coefficient of the output light intensity.

In various embodiments, variation of the Fourier coefficients as a function of the thickness of the target can be

determined in advance. FIG. 3a shows the results of such determination in accordance with an embodiment. In FIG. 3a, the angle θ is 75.55 degrees, and the light source 101 is a He—Ne laser and outputs light with wavelength 632.8 nm. FIG. 3a, shows variations in the Fourier coefficients as functions of thickness of the surface, when the thickness of the surface changes in the range of 0 to 500 nm. As seen in FIG. 3a, the Fourier coefficients are periodic functions of the surface thickness.

FIG. 3b shows the variations in the Fourier coefficients when the wavelength of the output light is 632.8 nm, the incident angle of the polarized light is 75.55 degrees, and when the thickness of the surface varies in the range of 0 to 50 nm. FIG. 3b shows that when the thickness is within 0 to 50 nm, the Fourier coefficient is a monotonic function of the surface thickness.

FIG. 4a shows the variations in the ellipsometry parameters $\tan \Psi$ and $\cos(\Delta)$ as a function of the thickness of the target. In FIG. 4a, the wavelength of the output light is 632.8 nm, the incident angle of the polarized light is 75.55 degrees, and the thickness of the surface varies in the range of 0 to 500 nm. FIG. 4a shows that when the thickness varies between 0 and 500 nm, the ellipsometric parameters $\tan \Psi$ and $\cos(\Delta)$ vary as periodic functions of the surface thickness.

FIG. 4b shows the variations of the ellipsometry parameters $\tan \Psi$ and $\cos(\Delta)$ as a function of the thickness of the target, when the wavelength of the output light is 632.8 nm, the incident angle of the polarized light is 75.55 degrees, and when the thickness of the surface varies in the range of 0 to 50 nm. FIG. 4b shows that, when the thickness is within the range 0 to 50 nm, the ellipsometry parameters $\tan \Psi$ and $\cos(\Delta)$ are monotonic functions of the surface thickness.

During the measurement process, the Fourier coefficient can be calculated based on equation (2). When all the azimuthal angles, including the polarized azimuthal angle, analyzer azimuthal angle, and the incident angle between the polarized light and the target surface are determined, and when the wavelength of the laser and also the refractive index of the target surface are known, all the Fourier coefficients α, β are thus known. Thus a control method can be used to find the specific Fourier coefficient within the range of values from the known Fourier coefficients that is most similar to the measured Fourier coefficients. Accordingly, the thickness of the target surface can be deduced to be equal to the thickness corresponding to the specific Fourier coefficient.

In theory, the Fourier coefficients α, β are functions of the thickness, the polarized light incident angle θ , the wavelength, light constants of the material of the target surface, the polarizer azimuthal angle and the analyzer azimuthal angle. In particular, the thickness, the polarized light incident angle θ , the wavelength, and light constants of the material of the target surface affect the ellipsometry parameters and the ellipsometry parameters in turn affect the Fourier coefficients. When using a fixed wavelength light source, and because the light constants of the material are fixed, their effects on the measurement can be ignored. Thus, the thickness of the target surface is the only factor that determines the Fourier coefficients α, β . Based on this principle, in a single range, Fourier coefficients vary with the thickness and each Fourier coefficient is a monotonic function of the thickness. Thus, according to the relationship between the Fourier coefficients and the thickness, the thickness can be calculated.

This exemplary embodiment describes the relationship between the Fourier coefficients and the ellipsometry parameters and the thickness when the light source 101 outputs light with the wavelength 632.8 nm, and the incident angle of the polarized light is 75.55 degrees. As is widely understood by

the persons of ordinary skill in the art, when the light wavelength and the incident angle are different, the relationship will change between the Fourier coefficients α, β on the one hand, and the ellipsometry parameters and the thickness on the other hand, but the principles of this disclosure will still be applicable.

Because, in addition to being related to the thickness of the target surface, each Fourier coefficient has a one-to-one relationship with the reflectivity, refractive index, extinction coefficient, polarization, surface microstructure, particles, defects and other surface roughness features as well, the methods of this disclosure are not limited to finding the thickness of the target surface, and other characteristics of the surface can also be measured. Persons of ordinary skill in the art can understand that methods and systems of this disclosure can also be used to measure other kinds of target surfaces and their characteristic information. Thus, for the sake of brevity, methods are not described for other situations.

The above-described embodiments show the measurement method when the fixed polarized azimuthal angle P and the fixed analyzer azimuthal angle A are all in the ideal state, that is $P=\pi/4$, $A=0, \pi/2$, and when $\theta=75.55$ degrees. In the process of real measurement, due to the deviation in the measuring device and the light path, this condition is difficult to achieve. Thus, when there is a deviation in polarized azimuthal angle, incident angle, or the fixed analyzer azimuthal angle, a calibration action must be taken on the deviation azimuthal angle, to determine the actual fixed polarized azimuthal angle, the incident angle, and the fixed analyzer azimuthal angle and, based on those actual values, to obtain the real thickness of the target surface.

To perform calibration, the method 500 of measuring the thickness of the target surface, shown in FIG. 5, will also include steps S20. In steps S20, calibration is performed at the fixed polarizer azimuthal angle, the incident angle, and the fixed-analyzer azimuthal angle to obtain the actual values of the fixed polarizer azimuthal angle, the incident angle, and the fixed-analyzer azimuthal angle. The method shown in FIG. 5 also includes the above-described steps S11 to S14, respectively labeled S11' to S14', for determining light intensity information about the p component and s component. Consequently, in step S15', based on the determined light intensity information about the p and s components, and also using the fixed polarizer azimuthal angle, the incident angle and the fixed analyzer azimuthal angle, the thickness of the target surface can be determined.

The calibration process for the polarized azimuthal angle, the analyzer azimuthal angle, and the incident angle shown is shown in FIG. 5 with some reference to FIGS. 1 and 2. Before the calibration, first target surface 105 should be replaced with a reference target surface 105' used for the calibration. Consistent with an embodiment, this reference target surface is preferably a SiO_2 film.

The calibration process works as follows. Supposing there is an azimuthal angle deviation between the polarizer and the analyzer, these angles are denoted as $P+\delta P$, $A+\delta A$, where δP represents the deviation between the actual azimuthal angle and the current theoretical value (e.g., $\pi/4$), and where δA represents the deviation between the actual analyzer azimuthal angle A and the current theoretical value (e.g., 0 and $\pi/2$). In this case, the output light intensity after passing through polarizer 103 and analyzer 107 is determined by the following equation:

7

$$\begin{aligned}
 I_{out}(P + \delta P, A + \delta A) &= I_0 \left(\frac{1 + \frac{\tan^2 \Psi - \tan^2(P + \delta P)}{\tan^2 \Psi + \tan^2(P + \delta P)} \cos 2(A + \delta A) + \frac{2 \tan \Psi \tan(P + \delta P) \cos \Delta}{\tan^2 \Psi + \tan^2(P + \delta P)} \sin 2(A + \delta A)}{1 + \frac{\alpha' \cos 2(A + \delta A) + \beta' \sin 2(A + \delta A)}{(\alpha' \cos 2\delta A + \beta' \sin 2\delta A) \cos 2A + (-\alpha' \sin 2\delta A + \beta' \cos 2\delta A) \sin 2A}} \right) \quad (3)
 \end{aligned}$$

in which,

$$\begin{aligned}
 \alpha' &= \frac{\tan^2 \Psi - \tan^2(P + \delta P)}{\tan^2 \Psi + \tan^2(P + \delta P)} \\
 \beta' &= \frac{2 \tan \Psi \tan(P + \delta P) \cos \Delta}{\tan^2 \Psi + \tan^2(P + \delta P)}
 \end{aligned}$$

represents the theoretical Fourier coefficients, and Δ is the phase difference between the p and s components of the characteristic light.

The theoretical value of the polarized azimuthal angle is $P = \pi/4$, its deviation is δP , the theoretical value of the analyzer azimuthal angle is $A = 0, \pi/2$, and its deviation is δA . Therefore, the two light intensities are,

$$I_1 = I(0) = I_{01}(1 + \alpha' \cos 2\delta A + \beta' \sin 2\delta A)$$

$$I_2 = I(\pi/2) = I_{01}(1 - \alpha' \cos 2\delta A - \beta' \sin 2\delta A) \quad (4)$$

Based on equation (4), the light intensity can be calculated as: $I_{01} = (I_1 + I_2)/2$

After normalization, the intensities are determined as:

$$I_1' = 1 + \alpha' \cos 2\delta A + \beta' \sin 2\delta A$$

$$I_2' = 1 - \alpha' \cos 2\delta A - \beta' \sin 2\delta A \quad (5)$$

Thus, the objective function is

$$X(\vec{t}, \delta P, \theta, \delta A, \vec{n}, \vec{k}, \lambda) = \sum_{i=1}^2 \sum_{j=1}^m (I_{ij}' - I_{ij}^{theory})^2 \quad (6)$$

where, \vec{t} is the thickness of the surface, θ is the incident angle, δP is the deviation of the polarizer azimuthal angle of the polarizer **103**, δA is the deviation of the analyzer azimuthal angle of the analyzer **107**, \vec{n} is the refractive index of the reference surface, \vec{k} is the extinction coefficient for the reference surface, and λ is the wavelength. In equation (6), I_{ij}' is the normalized obtained light intensity and I_{ij}^{theory} is the theoretically calculated light intensity. Further, in the sums of equation (6), the index i runs over the p and s components, and the index j runs over various the reference surfaces uses for calibration.

Considering the calibration equation (6), supposing that m reference surfaces with different known thicknesses are used for calibration, and that the wavelength of the used light is constant, then \vec{n}, \vec{k} will also be constant. Thus X has $2m$ variables. After removing the linear dependencies among related variables, there remains m variables that could be

8

used. There are 3 unknown variables including the variation in the polarized azimuthal angle δP , the incident angle θ and the analyzer azimuthal angle δA . Using the basic calculating method, all the unknown parameters could be found only when $m > 3$.

If one or more of the variables: polarizer **103**, azimuthal angle $P + \delta P$, incident angle θ , and the analyzer azimuthal angle $A + \delta A$ are known, then in the calibration step, remaining variables will be calibrated. Since the number of unknown parameters is high, then the required number of nonlinear equations and then the corresponding measurements on the reference surface time is reduced.

The above description and the related theory explained the principle of the calibration method provided by this disclosure. The following description addresses the steps in the calibration process, with reference to FIGS. **1** and **5**:

FIG. **5** shows a flow chart for a light division method for detecting characteristics information of a surface via the electromagnetic waves in accordance with an embodiment. In step **S201**, polarizer **103** polarizes the light at the fixed polarized azimuthal angle $P + \delta P$ to generate the polarized light. In step **S202**, the polarized light illuminates the known reference surface **105'** at the incident angle θ and is reflected off the surface as characteristic light. In step **S203**, analyzer **107** analyzes the characteristic light reflected from the reference surface **105'** at a fixed analyzed azimuthal angle $A + \delta A$, and separates the p and s components of the characteristic light. In step **S204**, detection-processing device **108** detects the light intensity of the p and s components of the characteristics light to obtain one set of light intensity information corresponding to reference surface **105'**.

In equation (6), the variables include the thickness of the reference surface \vec{t} , the deviation of the fixed polarizer azimuthal angle δP , the incident angle θ , the fixed polarizer azimuthal angle deviation δA , the refractive index \vec{n} of the reference surface **105'**, the light extinction coefficient \vec{k} of the reference surface **105'**, and the wavelength λ . Using numerical approximation methods, assuming the light intensity of the detected p and s components and the square of the sum of their corresponding theoretical light intensity deviation to be determined, equation (6) provides a nonlinear equation for finding the thickness of the reference surface **105'**.

Still referring to FIG. **5**, in step **S205**, based on the relationship between the foresaid function number and the unknown parameters number, and based on the nonlinear equations corresponding to the target surface **105'**, it is decided whether it is possible to determine all the unknown parameters, that is, the fixed polarized azimuthal angle $P + \delta P$, the incident angle θ , and the fixed analyzer azimuthal angle $A + \delta A$. If all those unknown parameters could not be determined, the reference surface **105'** will be replaced with another reference surface **105''**, and steps **S201** to **S205** will be repeated, until all the above listed unknown parameters, that is, azimuthal angle parameters in the fixed polarized azimuthal angle $P + \delta P$, the incident angle θ , and the fixed analyzer azimuthal angle $A + \delta A$ can be determined by solving a plurality nonlinear equations corresponding to a plurality of reference surfaces.

When it is possible to determine all the unknown parameters according to one or more nonlinear equations corresponding to one or more reference surfaces, the method shown in FIG. **5** moves to steps **S206**. Based on one or more nonlinear equations corresponding to the one or more reference surfaces, and using the relationships between the light intensity and surface characteristics information, derived

from nonlinear optimization theory, all of the unknown parameters are determined, that is, the polarized azimuthal angle $P+\delta P$, the incident angle θ , and the fixed analyzer azimuthal angle $A+\delta A$ are determined.

The calculating method could be the non-linear optimization method L-M, or could be any other method that could analyze the non-linear equations. The detailed calculation method depends on the available method. In some embodiments, the calculation process is performed by the calibration device 110. In some embodiments, the calibration device 110 could be a micro-processor that runs a program to perform the calibration process. Alternatively, in some other embodiments, the calibration device could be a corresponding firmware, ASIC, or DSP devices.

Independent of the above-described steps S201 to S205, and similar to steps S11 to S14 of FIG. 2, the process 500 also includes steps S11' to S14', as shown in FIG. 5. In steps S201 to S206, the light intensities of the p and s components, and the phase relationship information between the p and s component are determined. It is noted that all the azimuthal angles, that is, the fixed polarized azimuthal angle $P+\delta P$, the incident angle is θ and the fixed analyzer azimuthal angle $A+\delta A$, are the same during the detecting process (steps S11' to S15') and the calibration process (steps S20).

After determining the fixed polarized azimuthal angle $P+\delta P$, the incident angle θ , and the fixed analyzer azimuthal angle $A+\delta A$, the known light parameters of the reference surface 105', that is, \vec{n} and \vec{k} , and the detected azimuthal angle parameters, are inserted into equation (6) and, using the L-M method, the thickness is determined. Other nonlinear functions could also be used to determine the thickness, and the specific method does not change the focus of this disclosure. The calculating process could be completed by the calculating device 109. In various embodiments, calculating device 109 can be a microprocessing device performing the process for conducting the calibration process, or a firmware, ASIC, or DSP devices.

Second Embodiment

In the second embodiment, one or more dividers are installed between the surface and the analyzer along the light path. The one or more dividers divide the characteristics light reflected off the surface. The divided lights are polarized at a fixed azimuthal angle and their light intensities are detected. According to the light intensity of the p and s components of all the divided lights, the characteristic information of the target surface is determined.

FIG. 6 shows a light division ellipsometric system based on surface reflection for determining the characteristic information in accordance to the second embodiment. The system shown in FIG. 6 includes a light source 601, a first condenser hole 602, a polarizer 603 (at an azimuthal angle 45 degrees), a second condenser hole 604, a target surface 605 (preferred to be a SiO_2 film), a light divider 606, a first analyzer device 607a (at an azimuthal angle 0 degrees), and a first detection-processing device 608a. First detection processing device 608a receives the output of first polarizer 607a, wherein the output includes a p-polarized light component and an s-polarized light component, and detects the light intensity information of the s and p components, and also detects the phase relationship between the s and p components. The system in FIG. 6 further includes a second analyzer device 607b (at an azimuthal angle of 45 degrees), and a second detection-processing device 608b. Second detection-processing device 608b receives the output of second polarizer 607b, wherein

the output includes a p-polarized light component and an s-polarized light component. Second detection-processing device 608b further detects the light intensity information of the s and p components and the phase relationship between the s and p components. Polarized light incident angle θ is near the target surface Brewster azimuthal angle. Further, in the system shown in FIG. 6, first and second detection-processing units 608a and 608b are connected to a computing device 609 and a calibration device 611, which are not shown in FIG. 6.

In the embodiment shown in FIG. 6, light source 601 uses a He—Ne laser with an output light wavelength of 632.8 nm. As understood by persons of ordinary skill in the art, light source 601 is not limited to the He—Ne laser, and can include other high-power red LED light sources. First condenser hole 602 is used to better focus the incident light. However, as known by persons of ordinary skill in the art, first condenser hole 602 is not necessary to implement the embodiments. Second condenser hole 604 is used to prevent partial output from other polarized light beams into the measurement light path, and thus to avoid the impact of those outputs on the measurement results. Further, as also known by persons of ordinary skill in the art, second condenser hole 604 is also not necessary to implement the embodiments. Usually, the use of first and second condenser holes 602 and 604 help to improve accuracy of the measurements of the surface characteristics information by the electromagnetic waves.

FIG. 7 shows a flow chart for a light division method for detecting characteristics information of a surface via the electromagnetic waves. In particular, the method 700 uses surface reflection and light division ellipsometry techniques, consistent with an embodiment. The following description describes steps of the ellipsometry measurement method for a target surface- SiO_2 film, in relation to FIGS. 6 and 7. That is, in this embodiment, the characteristic information of the target surface is the thickness of the target.

First, at the start of the method, light source 601 emits light, the emitted light goes through first condenser hole 602, is focused hole 602, and then illuminates polarizer 603. In step S31, polarizer 603 polarizes a single wavelength light at a fixed polarizer azimuthal angle P to generate a polarized light. Then, the polarized light goes through second condenser hole 604. Second condenser hole 604 only allows one polarized light passed through polarizer 603, and blocks the rest of polarized lights in order to avoid their impact on the measurement. Thus, in step S32, the polarized light is incident at the incident angle θ onto target surface 605. As known by persons of ordinary skill in the art, without condenser hole 604, the light path of the polarized light pass through polarizer 603 may be quite different from the light path of the polarized light passed through second condenser as shown in FIG. 6. However, in the first case, the additional light will not be reflected by target surface 605 and thus will not reach first and second analyzers 607a and 607b. So the effect to the measurement result can be ignored, or even this effect will not be generated. So, as mentioned above, second condenser hole 604 is not necessary.

The illuminated polarized light is reflected by target surface 605 as a result of which the nature of this polarized light changes. In step S33, light divider 606 divides the characteristics light, which is reflected by the target surface, to generate the corresponding characteristic lights L_1 and L_2 , and then divided light L_1 and L_2 reach two analyzers 607a and 607b.

In step S34, first analyzer 607a analyzes characteristics light L_1 at the fixed analyzer azimuthal angle, separates the p_1 and s_1 components, which are the p and s component of the L_1 , and then provides p_1 and s_1 to second detection-process-

ing device **608a**. Second analyzer **607b** analyzes characteristics light L_2 at the fixed analyzer azimuthal angle, separates the p_2 and s_2 components, which are the p and s components of light L_2 , and then provides p_2 and s_2 to second detection-processing device **608b**.

In step S35, first and second detection-processing devices **608a** and **608b** receive and detect the light intensity of the p_1 and s_1 , and p_2 and s_2 components, obtain the light intensity information corresponding to the target surface, and obtain the phase difference between the p_1 and s_1 components, and the phase difference between the p_2 and s_2 components. First and second detection processing devices **608a** and **608b** then provide the obtained light intensity information to calculation device **609**, which has electromagnetic connections with first and second detection-processing devices **608a** and **608b**, and is not shown in FIG. 6. Specifically, first and second detection-processing devices **608a** and **608b** may include light intensity detecting devices and the processing devices, wherein the light intensity detecting device is used to detect the light intensity of the p component and the s component of the detected characteristics lights L_1 and L_2 , and the processing device is used to obtain the phase differences between the p and the s components, p_1 and s_1 or p_2 and s_2 .

Finally, in step S36, calculating device **609**, using the light intensity of the p_1 and s_1 components and the p_2 and s_2 components, determines the thickness of the target surface using a predetermined method. It can be understood by persons of ordinary skill in the art that there are several ways to determine the thickness information, and the method is not limited to those detailed in this embodiment. Consistent with an embodiment, the principles of this determination method are as follows.

The basic equation for the intensity of the output light after passing through the polarizer and the analyzer is

$$I_{out}(P, A) = I_0 \left(1 + \frac{\tan^2 \Psi - \tan^2 P}{\tan^2 \Psi + \tan^2 P} \cos 2A + \frac{2 \tan \Psi \tan P \cos \Delta}{\tan^2 \Psi + \tan^2 P} \sin 2A \right) \quad (7)$$

For the light passing through the analyzer **607a**, $P=\pi/4$, $A=A_1=0, \pi/2$, $\tan \Psi$ is the amplitude ratio of the p and s components of the light, and A is the phase difference between the p and s components. Light intensities $I(\pi/4, 0)_{out}$ and $I(\pi/4, \pi/2)_{out}$ can be used to calculate the Fourier coefficient

$$\alpha = \frac{\tan^2 \Psi - 1}{\tan^2 \Psi + 1},$$

and to further calculate the ellipsometric parameters $\tan \Psi$, that is:

$$\alpha = \frac{I(\pi/4, 0)_{out} - I(\pi/4, \pi/2)_{out}}{I(\pi/4, 0)_{out} + I(\pi/4, \pi/2)_{out}}, \quad (8)$$

$$\tan \Psi = \frac{I(\pi/4, 0)_{out}}{I(\pi/4, \pi/2)_{out}}$$

For the light passing through analyzer **607b**, $P=\pi/4$, $A=A_2=\pm\pi/4$, which, from equation (7), results in light intensities $I(\pi/4, \pi/4)_{out}$ $I(\pi/4, -\pi/4)_{out}$. Moreover,

$$\beta = \frac{2 \tan \Psi \cos \Delta}{\tan^2 \Psi + 1}$$

stands for the first-order Fourier coefficient. Therefore,

$$\beta = \frac{I(\frac{\pi}{4}, \frac{\pi}{4})_{out} - I(\frac{\pi}{4}, -\frac{\pi}{4})_{out}}{I(\frac{\pi}{4}, \frac{\pi}{4})_{out} + I(\frac{\pi}{4}, -\frac{\pi}{4})_{out}} \quad (9)$$

Consistent with an embodiment, the Fourier coefficient can be calculated in advance. The variations of the Fourier coefficients α, β for different thicknesses are similar to those discussed for the first embodiment. When the incident angle θ is 75.55 degrees, the helium-neon laser outputs the incident light of 632.8 nm wavelength, the variations of the Fourier coefficients and of the ellipsometry parameters are similar to those shown in FIGS. 3a, 3b, 4a, and 4b.

The above-described embodiments show the measurement method when the fixed polarized azimuthal angle P and the fixed analyzer azimuthal angles A_1 and A_2 are all in the ideal state, that is $P=\pi/4, A_1=0, \pi/2, A_2=\pm\pi/4$, and when $\theta=75.55$ degrees. In the process of real measurement, due to the deviation in the measuring device and the light path, this condition is difficult to achieve. Thus, when there is a deviation in polarized azimuthal angle P , incident angle θ , or the fixed analyzer azimuthal angles A_1 and A_2 , a calibration action must be taken to determine the deviation in the fixed polarized azimuthal angle P and the incident angle θ , and based on the determined fixed polarized azimuthal angle P and the incident angle θ , to obtain the thickness of the target surface.

To perform calibration, a method of measuring the thickness of the target surface, shown in FIG. 8, will also include steps S40. In steps S40, calibration is performed at the fixed polarizer azimuthal angle, the incident angle and the fixed-analyzer azimuthal angles A_1 and A_2 , to obtain the actual value of the fixed polarizer azimuthal angle, the incident angle, and the fixed-analyzer azimuthal angle. The method of FIG. 8 also includes the above-described steps S31 to S35, labeled as steps S31' to S35', respectively, for determining light intensity information about the p_1, s_1, p_2 , and s_2 components. Consequently, in step S36', based on the determined light intensity information about p_1 and s_1 components and p_2 and s_2 components, and also using the fixed polarizer azimuthal angle, the incident angle, and the fixed analyzer azimuthal angle, the thickness of the target surface can be determined.

Below is described the method of calibration for the polarized azimuthal angle, the analyzer azimuthal angle, and the incident angle. Based on the obtained azimuthal angles and on the obtained light intensities of the p and s components, the thickness is measured.

In FIG. 8, steps S40 show the calibration flow chart for the calibration method of the polarized azimuthal angle, the analyzer azimuthal angle, and the incident angle for the system shown in FIG. 6, which uses the surface reflection and light division technique. The calibration process in accordance with an embodiment is described below.

Before the calibration, first target surface **605** in FIG. 6 is replaced with reference surface **605'** used for calibration. The calibration process works as follows. Supposing there is an azimuthal angle deviation between polarizer **603** and analyzers **607a** and **607b**, these angles are denoted as $P+\delta P, A_1+\delta A_1$ and $A_2+\delta A_2$, where δP represents the deviation between the

13

actual azimuthal angle P and the current theoretical value (e.g., $\pi/4$), and δA_1 and δA_2 respectively represent the deviations between the actual analyzer azimuthal angles A_1 and A_2 and the current theoretical value (e.g., 0 and $\pi/2, \pi/4$ and $-\pi/4$). The output light intensity is thus determined by the following equation:

$$I_{out}(P + \delta P, A + \delta A) = I_0 \left(\frac{1 + \frac{\tan^2 \Psi - \tan^2(P + \delta P)}{\tan^2 \Psi + \tan^2(P + \delta P)} \cos 2(A + \delta A) + \frac{2 \tan \Psi \tan(P + \delta P) \cos \Delta}{\tan^2 \Psi + \tan^2(P + \delta P)} \sin 2(A + \delta A) \right) \quad (10)$$

$$= \left(\frac{1 + \alpha' \cos 2(A + \delta A) + \beta' \sin 2(A + \delta A)}{\beta' \sin 2(A + \delta A)} \right)$$

$$= \left(\frac{1 + (\alpha' \cos 2\delta A + \beta' \sin 2\delta A) \cos 2A + (-\alpha' \sin 2\delta A + \beta' \cos 2\delta A) \sin 2A}{\beta' \sin 2\delta A} \right)$$

in which

$$\alpha' = \frac{\tan^2 \Psi - \tan^2(P + \delta P)}{\tan^2 \Psi + \tan^2(P + \delta P)}$$

$$\beta' = \frac{2 \tan \Psi \tan(P + \delta P) \cos \Delta}{\tan^2 \Psi + \tan^2(P + \delta P)}$$

represents the theoretical Fourier coefficients, and Δ is the phase deviation between the p and s component for the characteristic light.

The theoretical value of the polarized azimuthal angle is $P = \pi/4$, its deviation is δP , the theoretical value of the analyzer **607a** azimuthal angle A_1 is $00/90^\circ$, its deviation is δA_1 , the theoretical value of the analyzer **607b** azimuthal angle A_2 is $45^\circ/-45^\circ$, and its deviation is δA_2 . Therefore, the 4 light intensities are

$$I_1 = I(0) = I_{01}(1 + \alpha' \cos 2\delta A_1 + \beta' \sin 2\delta A_1)$$

$$I_2 = I(\pi/2) = I_{01}(1 - \alpha' \cos 2\delta A_1 - \beta' \sin 2\delta A_1)$$

$$I_3 = I(\pi/4) = I_{02}(1 - \alpha' \sin 2\delta A_2 + \beta' \cos 2\delta A_2)$$

$$I_4 = I(-\pi/4) = I_{02}(1 + \alpha' \sin 2\delta A_2 - \beta' \cos 2\delta A_2)$$

After the normalization, the light intensities are determined as:

$$I'_1 = \frac{I_1}{I_{01}} = 1 + \alpha' \cos 2\delta A_1 + \beta' \sin 2\delta A_1 \quad (12)$$

$$I'_2 = \frac{I_2}{I_{01}} = 1 - \alpha' \cos 2\delta A_1 - \beta' \sin 2\delta A_1$$

$$I'_3 = \frac{I_3}{I_{02}} = 1 - \alpha' \sin 2\delta A_2 + \beta' \cos 2\delta A_2$$

$$I'_4 = \frac{I_4}{I_{02}} = 1 + \alpha' \sin 2\delta A_2 - \beta' \cos 2\delta A_2$$

Thus the objective function is,

$$X(\vec{t}, \delta A_1, \delta A_2, \delta P, \vec{n}, \vec{k}, \lambda) = \sum_{i=1}^4 \sum_{j=1}^m (I'_{ij} - I_{ij}^{theory})^2 \quad (13)$$

in which \vec{t} is the thickness of the surface, θ is the incident angle, δP is the deviation of the polarizer azimuthal angle of polarizer **3**, δA_1 is the deviation of the analyzer azimuthal

14

angle for first analyzer **607a**, δA_2 is the deviation of the analyzer azimuthal angle for second analyzer **607b**, \vec{n} is the refractive index of the reference surface, \vec{k} is the extinction coefficient for the reference surface, and λ is the wavelength. In equation (13), I'_{ij} is the normalized obtained light intensity and I_{ij}^{theory} is the theoretically calculated light intensity. Further, in the sums in equation (13), the index i runs over the p_1 and s_1 , p_2 , and s_2 components, and the index j runs over various reference surfaces used for calibration.

Considering calibration equation (6), supposing that m reference surfaces with different known thicknesses are used for calibration, and that the wavelength of the used light is constant, then \vec{n} , \vec{k} will also be constant. Thus, X has $4m$ variables. After removing the linear dependencies among related variables, there remains $2m$ variables that could be used. There are $m+4$ unknown variables including the variations δP , δA_1 , δA_2 , the incident angle θ , and m unknown thicknesses of the reference target surfaces. Using the basic calculating method, all the unknown parameters could be found only when $2m > m+4$, that is $m > 4$.

If one or more of polarizer **603** azimuthal angle $P + \delta P$, incident angle θ , and analyzer azimuthal angles $A_1 + \delta A_1$ and $A_2 + \delta A_2$ of the first and second analyzers **607a** and **607b** are known, then in the calibration step, the remaining variables can be calibrated. Since the number of unknown parameters is not high, then the required number of nonlinear equations and then the corresponding measurements on the reference surface time is reduced.

Above, the calibration and its supporting theory were described in accordance with the embodiments. The following detailed description describes the steps in the calibration process, in reference to FIGS. **8** and **6**.

In step **S401**, polarizer **603** polarizes the light at the fixed polarized azimuthal angle $P + \delta P$ to generate the polarized light. In step **S402**, the polarized light illuminates the known reference surface **605'** at the incident angle θ and is reflected off the surface as characteristic light. In step **S404**, light divider **606** divides the characteristics light to generate divided characteristic lights L_1 and L_2 .

In step **S404**, analyzers **607a** and **607b** analyze characteristic lights L_1 and L_2 at fixed analyzed azimuthal angles $A_1 + \delta A_1$ and $A_2 + \delta A_2$, respectively, and analyze the p_1 and s_1 , and p_2 and s_2 , components of characteristic light L_1 and L_2 .

In step **S405**, first and second detection-processing devices **608a** and **608b** detect the light intensity of the p_1 and s_1 , and p_2 and s_2 , components to obtain the light intensity information corresponding to reference surface **605'**.

In equation (13), the variables include the thickness of the reference surface **605'**, the fixed polarizer azimuthal angle $P + \delta P$, the incident angle θ , the fixed analyzer azimuthal angle $A_1 + \delta A_1$ and $A_2 + \delta A_2$, the refractive index \vec{n} of the reference surface **605'**, the light extinction coefficient \vec{k} of the reference surface **605'**, and the wavelength λ . Using numerical approximation methods, assuming the light intensity of the detected p and s components and the square of the sum of the corresponding theoretical light intensity deviation to be determined, equation (13) provides a nonlinear equation for finding the thickness of the reference surface **605'**.

In step **S406**, based on the relationship between the fore-said function number and the unknown parameters number, and based on the nonlinear equations corresponding to the reference surface **605'**, it is decided whether it is possible to determine all the unknown parameters, that is, the fixed polarized azimuthal angle $P + \delta P$, the incident angle θ , and the fixed analyzer azimuthal angles $A_1 + \delta A_1$ and $A_2 + \delta A_2$. If all of them

15

could not be determined, the reference surface **605'** will be replaced with another reference surface **605''**, and steps **S401** to **S406** will be repeated, until all the above-listed unknown parameters, that is, azimuthal angle parameters in the fixed polarized azimuthal angle $P+IP$, the incident angle θ and fixed analyzer azimuthal angles $A_1+\delta A_1$ and $A_2+\delta A_2$ can be determined by solving a plurality of nonlinear equations corresponding to the plurality of reference surfaces.

When it is possible to determine all the unknown azimuthal angle parameters according to one or more nonlinear equation (13) corresponding to one or more reference surfaces, the method moves to step **S407**. In step **S407**, based on one or more nonlinear equations corresponding to one or more reference surfaces, and using the relationships between the light intensity and surface characteristics information, derived from nonlinear optimization theory methods, all of the unknown parameters are determined, that is, the polarized azimuthal angle $P+\delta P$, the incident angle θ , and the fixed analyzer azimuthal angles $A_1+\delta A_1$ and $A_2+\delta A_2$ are determined. The calculating method could be the non-linear optimization method L-M, or could be any other method that could analyze the non-linear equations. The detailed calculation method depends on the available method. Consistent with an embodiment, calibration device **611** performs the calculating process.

Independent of the above-described steps **S401** to **S407** and steps **S31** to **S35**, the calibration process also includes steps **S31'** to **S35'**, as shown in FIG. 8. In steps **S31'** to **S35'**, light intensities of the p_1 and s_1 , p_2 and s_2 , components are determined. It is noted that all the azimuthal angles, that is, the fixed polarized azimuthal angle is $P+\delta P$, the incident angle is θ , and the fixed analyzer azimuthal angles $A_1+\delta A_1$ and $A_2+\delta A_2$ are the same during the detecting process (steps **S31'**-**S35'**) and the calibration process (steps **S401**-**S407**).

After determining the fixed polarized azimuthal angle $P+\delta P$, the incident angle θ , and the fixed analyzer azimuthal angles $A_1+\delta A_1$ and $A_2+\delta A_2$, in step **S36'**, the known light parameters of the reference surface **605**, that is, \vec{n} and \vec{k} , and the detected azimuthal angle parameters, are inserted into equation (13), and using the L-M method the thickness is determined. In some embodiments, the calculating process is performed by the calculating device **609**. Of course, other nonlinear functions could be used to determine this thickness, and the detailed determination method is not the focus of this disclosure.

In another embodiment, the ellipsometry measurement device stores one or more characteristic information and the ellipsometric parameters, such as P and A in a measurement database. Specifically, after the system calibration with above method, the obtained characteristic information of several target surfaces in the same conditions and their corresponding ellipsometric parameters are stored along with their corresponding relationship. In another embodiment, the corresponding relationship may be conducted from the outside. Then, when the characteristic information of the target surface by the electromagnetic waves, the azimuthal angle of the ellipsometric measurement remain constant, use the obtained corresponding ellipsometric parameters corresponding to the current target surface, based on the corresponding relationship between the ellipsometric parameters and the characteristic information pre-reserved in the database, the characteristic information could be obtained from this corresponding relationship by the obtained ellipsometric parameters.

The above description is a method, after using the target reflection change the ellipsometric state of the incident light, after the measurement for the characteristic information of

16

the reflected characteristic light, of the characteristic information confirmation. This invention is not limited to the method of using the target reflection change the ellipsometric state of the incident light, besides, the using the target transmittance or diffraction change the ellipsometric state of the incident light, to get the corresponding characteristic light information then get the target characteristics.

FIG. 9 shows a system in accordance with an embodiment. The system of FIG. 9 includes a light source **901**, a first condenser hole **902**, a polarizer **903** (at an azimuthal angle of 45 degrees), a second condenser hole **904**, a target surface **905** (preferred to be the SiO_2 film), a light divider **906**, a first analyzer device **907a** (at an azimuthal angle of 0 degrees), and a first detection-processing device **908a**. First detection-processing device **8a** receives the output of first polarizer **907a**, wherein the output is includes a p-polarized light component and an s-polarized light components, and detects the light intensity information of the s and p components and also detects the phase relationship between the s and p components. The system of FIG. 9 also includes a second analyzer device **907b** (at an azimuthal angle of 45 degrees), and a second detection-processing device **908b**. Second detection-processing device **908b** receives the output of second polarizer **907b**, wherein the output includes p polarized and s-polarized light components. Second detection-processing device **908b** further detects the light intensity information of the s and p components and determines the phase relationship between the s and p components. Polarized light incident angle θ is near the target surface Brewster azimuthal angle. Further, in the system of FIG. 9, first and second detection-processing units **908a** and **908b** are connected to a computing device **909**, which is not shown. The steps of the ellipsometry measurement method for determining the target surface thickness, and the fixed polarized azimuthal angles, the incident angle, or the calibration process are all similar with the previously described second embodiment. It is understood in this field that, the light divider **906**, the analyzer **907b**, and the detection-processing device **908b** could be eliminated, in which case, the ellipsometric measurement steps for the target surface thickness and the calibration measurement steps will all be similar to the first embodiment, and will not be described again.

FIG. 10 shows a system consistent with an embodiment, using light division ellipsometry light road map of surface diffraction and light division techniques for the characteristic information identification by electromagnetic waves. Various sections of the system are similar to the corresponding sections of the system shown in FIG. 6. The system shown in FIG. 10 can be used in a manner similar to that described for the second embodiment. It is understood in this field that, light divider **1006**, analyzer **1007b**, and the detection-processing device **1008b** could be eliminated, with the methods applied to system of FIG. 10 being similar to those described for the first embodiment.

It is understood that the disclosed embodiments are not limited to light reflection techniques, light transmission techniques, or light diffraction techniques. It is to be understood that this invention can be used to obtain polarized light characteristics via reflection, transmission, or diffraction, and then based on the obtained light characteristics to obtain the characteristic information of the target surface by electromagnetic waves. Using general techniques of this disclosure, the calibration and measurement steps of the ellipsometric measurement method can be improved. The methods of the invention are not limited of one of above-disclosed embodiments, and all kinds of variations or modifications could be applied to arrive at the scope of the following claims.

17

What is claimed is:

1. A method for measuring a value of a characteristic of a target surface based on ellipsometry techniques, the method comprising:

polarizing incident light via a polarizer adjusted at a polarizer azimuthal angle to generate polarized light; 5
illuminating via the polarized light the target surface at an incident angle to generate characteristic light;
analyzing the characteristic light via an analyzer at an analyzer azimuthal angle to obtain a p-component of the characteristic light and an s-component of the characteristic light; 10
detecting a first light intensity corresponding to the p-component and a second light intensity corresponding to the s-component; 15
detecting a phase relationship between the p-component and the s-component; and
determining the value of the characteristic for the target surface based on a first relationship that is among the value of the characteristic, the first light intensity, the second light intensity, and the phase relationship, wherein the determining of the value of the characteristic for the target surface comprises: 20
calculating one or more values for one or more of (a) a Fourier coefficient or (b) an ellipsometry coefficient for the first light intensity and the second light intensity; and 25
using a monotonic relationship between the value of the characteristic and the calculated one or more values to obtain the value of the characteristic, 30

wherein the analyzing of the characteristic light, the detecting of the first light intensity and the second light intensity, the detecting of the phase relationship, and the determining of the value further comprise: 35

dividing the characteristic light via a divider into a plurality of divided characteristic lights; 35
for each of the plurality of divided characteristic lights:
obtaining, via one of a plurality of analyzers, a divided p-component and a divided s-component; 40
detecting a first divided light intensity corresponding to the divided p-component and a second divided light intensity corresponding to the divided s-component; and
detecting a divided phase relationship between the divided p-component and the divided s-component; and 45

determining the value of the characteristic for the target surface based on a second relationship that is among the value of the characteristic and the first divided light intensity, the second divided light intensity, and the divided phase relationship for each of the plurality of divided characteristic lights; 50

wherein a first one of the plurality of analyzers analyzes a first one of the plurality of divided characteristic lights at a first fixed analyzer azimuthal angle, and a second one of the plurality of analyzers analyzes a second one of the plurality of divided characteristic lights at a second fixed analyzer azimuthal angle, a difference between the first fixed analyzer azimuthal angle and the second fixed analyzer azimuthal angle being $\pi/4$. 55

2. The method of claim 1, further comprising calibrating to determine one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident angle. 65

3. The method of claim 2, wherein the calibrating comprises:

18

polarizing the incident light via the polarizer adjusted at the polarizer azimuthal angle to generate polarized light;
illuminating via the polarized light a calibrating target surface at the incident angle to generate a calibrating characteristic light, wherein a value of the characteristic for the calibrating target surface is known;

analyzing the calibrating characteristic light via the analyzer at the analyzer azimuthal angle to obtain a calibrating p-component of the calibrating characteristic light and a calibrating s-component of the calibrating characteristic light;

detecting a first calibrating light intensity corresponding to the calibrating p-component and a second calibrating light intensity corresponding to the calibrating s-component;

detecting a calibrating phase relationship between the calibrating p-component and the calibrating s-component; and

determining one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident angle based on a third relationship that is among the value of the characteristic for the calibrating target surface, the first calibrating light intensity, the second calibrating light intensity, and the calibrating phase relationship.

4. The method of claim 1, further comprising calibrating to determine one or more of the polarizer azimuthal angle, a plurality of analyzer azimuthal angles each for one of the plurality of analyzers, and the incident light.

5. The method of claim 4, wherein the calibrating comprises:

polarizing the incident light via the polarizer adjusted at the polarizer azimuthal angle to generate polarized light;
illuminating via the polarized light a calibrating target surface at the incident angle to generate a calibrating characteristic light, wherein a value of the characteristic for the calibrating target surface is known;

dividing the calibrating characteristic light via the divider into a plurality of divided calibrating characteristic lights;

for each of the plurality of divided calibrating characteristic lights:

obtaining, via one of the plurality of analyzers, a divided calibrating p-component and a divided calibrating s-component;

detecting a first divided calibrating light intensity corresponding to the divided calibrating p-component and a second divided calibrating light intensity corresponding to the divided calibrating s-component;

detecting a divided calibrating phase relationship between the divided calibrating p-component and the divided calibrating s-component; and

determining one or more of the polarizer azimuthal angle, the incident light, and the plurality of azimuthal angles for the plurality of analyzers based on a third relationship that is among the value of the characteristic for the calibrating target surface, the first divided calibrating light intensity, the second divided calibrating light intensity, and the divided calibrating phase relationship for each of the plurality of divided calibrating characteristic lights.

6. The method of claim 1, wherein calculating the one or more values comprises applying numerical approximation to derive the monotonic relationship.

7. The method of claim 1, wherein the characteristic light results from one or more of reflection, transmission, or diffraction of the polarized light by the target surface.

19

8. The method of claim 7, further comprising calibrating to determine one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident angle.

9. The method of claim 8, wherein the calibrating comprises:

polarizing the incident light via the polarizer adjusted at the polarizer azimuthal angle to generate polarized light; illuminating via the polarized light a calibrating target surface at the incident angle to generate a calibrating characteristic light, wherein a value of the characteristic for the calibrating target surface is known;

analyzing the calibrating characteristic light via the analyzer at the analyzer azimuthal angle to obtain a calibrating p-component of the calibrating characteristic light and a calibrating s-component of the calibrating characteristic light;

detecting a first calibrating light intensity corresponding to the calibrating p-component and a second calibrating light intensity corresponding to the calibrating s-component;

detecting a calibrating phase relationship between the calibrating p-component and the calibrating s-component; and

determining one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident angle based on a third relationship that is among the value of the characteristic for the calibrating target surface, the first calibrating light intensity, the second calibrating light intensity, and the calibrating phase relationship.

10. A light division ellipsometry system for measuring a value of a characteristic of a target surface based on ellipsometry techniques, the system comprising:

a polarizer adjustable to a polarizer azimuthal angle to polarize incident light to generate polarized light to illuminate the target surface at an incident angle and generate characteristic light;

an analyzer adjustable to an analyzer azimuthal angle to analyze the characteristic light to obtain a p-component of the characteristic light and an s-component of the characteristic light;

an intensity detector to detect a first light intensity corresponding to the p-component and a second light intensity corresponding to the s-component;

a phase detector to detect a phase relationship between the p-component and the s-component; and

a processing device to determine the value of the characteristic for the target surface based on a first relationship that is among the value of the characteristic, the first light intensity, the second light intensity, and the phase relationship, wherein the processing device determines the value of the characteristic for the target surface by:

calculating one or more values for one or more of (a) a Fourier coefficient or (b) an ellipsometry coefficient for the first light intensity and the second light intensity; and

20

using a monotonic relationship between the value of the characteristic and the calculated one or more values to obtain the value of the characteristic,

wherein the system further comprises:

a divider to divide the characteristic light into a plurality of divided characteristic lights; and

for each of the plurality of divided characteristic lights:

one of a plurality of analyzers to obtain a divided p-component and a divided s-component;

a division light detector to detect a first divided light intensity corresponding to the divided p-component and a second divided light intensity corresponding to the divided s-component; and

a division phase detector to detect a divided phase relationship between the divided p-component and the divided s-component,

wherein the processing device determines the value of the characteristic based on a second relationship that is among the value of the characteristic and the first divided light intensity, the second divided light intensity, and the divided phase relationship for each of the plurality of divided characteristic lights; and

wherein a first one of the plurality of analyzers analyzes a first one of the plurality of divided characteristic lights at a first fixed analyzer azimuthal angle, and a second one of the plurality of analyzers analyzes a second one of the plurality of divided characteristic lights at a second fixed analyzer azimuthal angle, a difference between the first fixed analyzer azimuthal angle and the second fixed analyzer azimuthal angle being $\pi/4$.

11. The system of claim 10, wherein the characteristic light results from one or more of reflection, transmission, or diffraction of the polarized light by the target surface.

12. The system of claim 10, further comprising a calibrator to determine one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident light.

13. The system of claim 12, wherein the calibrator determines one or more of the polarizer azimuthal angle, the analyzer azimuthal angle, and the incident angle based on a third relationship that is among a value of the characteristic for a calibrating target surface for which the value of the characteristic is known, a first calibrating light intensity, a second calibrating light intensity, and a calibrating phase relationship, wherein the first calibrating light intensity, the second calibrating light intensity, and the calibrating phase relationship are derived by applying the light division ellipsometry system to the calibrating target surface.

14. The system of claim 10, further comprising a calibrator to determine one or more of the polarizer azimuthal angle, a plurality of analyzer azimuthal angles each for one of the plurality of analyzers, and the incident light.

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